

**INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION**

(PTO-1449)



ATTY. DOCKET NO.
5920/FET/DV

SERIAL NO.
09/943,383

APPLICANT
SHANMUGASUNDRAM et al.

FILING DATE
August 31, 2001

GROUP

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| | 5,089,970 | 02/18/92 | Lee et al. | | | 10/05/89 |
| | 5,108,570 | 04/28/92 | Wang | | | 03/30/90 |
| | 5,220,517 | 06/15/93 | Sierk et al. | | | 08/31/90 |
| | 5,236,868 | 08/17/93 | Nulman | | | 04/20/90 |
| | 5,260,868 | 11/09/93 | Gupta et al. | | | 10/15/91 |
| | 5,295,242 | 03/15/94 | Mashruwala et al. | | | 11/02/90 |
| | 5,309,221 | 05/03/94 | Fischer et al. | | | 12/31/91 |
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| | 5,398,336 | 03/14/95 | Tantry et al. | | | 06/16/93 |
| | 5,402,367 | 03/28/95 | Sullivan et al. | | | 07/19/93 |
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| | | | | | | Yes | No |
| D | 01-283934 | 11/15/89 | Japan | | | X | |
| | 2,050,247 | 08/29/91 | Canada | | | X | |

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| | 5,661,669 | 08/26/97 | Mozumder et al. | | | 06/07/95 |
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| | 5,719,495 | 02/17/98 | Moslehi | | | 06/05/96 |
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| | | | | | | Yes | No |
| | 2,165,847 | 08/29/91 | Canada | | | X | |
| | 2,194,855 | 08/29/91 | Canada | | | X | |

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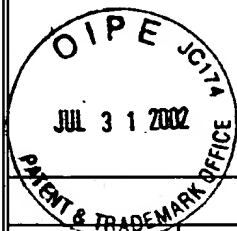
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| | 5,910,011 | 06/08/99 | Cruse | | | 05/12/97 |
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|--|---------------|----------|---------|-------|----------|-------------|----|
| | | | | | | Yes | No |
|  | 05-151231 | 06/18/93 | Japan | | | | X |
| | 05-216896 | 08/27/93 | Japan | | | | X |
| | 05-266029 | 10/15/93 | Japan | | | | X |
| | 06-110894 | 04/22/94 | Japan | | | | X |
| | 06-176994 | 06/24/94 | Japan | | | | X |
| | 06-252236 | 09/09/94 | Japan | | | | X |
| | 06-260380 | 09/16/94 | Japan | | | | X |
| | 08-149583 | 06/07/96 | Japan | | | X | |
| | 09-34535 | 02/07/97 | Japan | | | X | |
| | EP 0877308 A2 | 11/11/98 | Europe | | | X | |
| | 11-67853 | 03/09/99 | Japan | | | X | |
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| | 12/9/03 |

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| INFORMATION DISCLOSURE CITATION IN AN APPLICATION | | | | ATTY. DOCKET NO. 5920/FET/DV | | SERIAL NO. 09/943,383 | |
|  | | | | APPLICANT SHANMUGASUNDRAM et al. | | | |
| | | | | FILING DATE August 31, 2001 | | GROUP | |
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| D | 09/363,966 | 07/29/99 | Arackaparambil et al. | Computer Integrated Manufacturing Techniques | | | |
| D | 09/469,227 | 12/22/99 | Somekh et al. | Multi-Tool Control System, Method and Medium | | | |
| D | 09/619,044 | 07/19/00 | Yuan | System and Method of Exporting or Importing Object Data in a Manufacturing Execution System | | | |
| D | 09/637,620 | 08/11/00 | Chi et al. | Generic Interface Builder | | | |
| D | 09/656,031 | 09/06/00 | Chi et al. | Dispatching Component for Associating Manufacturing Facility Service Requestors with Service Providers | | | |
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| | 09/655,542 | 09/06/00 | Yuan | System, Method and Medium for Defining Palettes to Transform an Application Program Interface for a Service | | |
| | 09/725,908 | 11/30/00 | Chi et al. | Dynamic Subject Information Generation in Message Services of Distributed Object Systems | | |
| | 09/800,980 | 03/08/01 | Hawkins et al. | Dynamic and Extensible Task Guide | | |
| | 09/811,667 | 03/20/01 | Yuan et al. | Fault Tolerant and Automated Computer Software Workflow | | |
| | 09/927,444 | 08/13/01 | Ward et al. | Dynamic Control of Wafer Processing Paths in Semiconductor Manufacturing Processes | | |
| | 09/928,473 | 08/14/01 | Koh | Tool Services Layer for Providing Tool Service Functions in Conjunction with Tool Functions | | |

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|---------------------|------------|------|---------|-------|-----------|-------------|----|
| | | | | | | Yes | No |
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U.S. PATENT DOCUMENTS

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| | 09/928,474 | 08/14/01 | Krishnamurthy et al. | Experiment Management System, Method and Medium | | |
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| EXAMINER'S INITIALS | PATENT NO. | DATE | COUNTRY | CLASS | SUB- CLASS | Translation |
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| | | | | | | Yes No |
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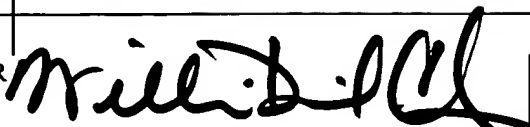
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| EXAMINER'S INITIALS | PATENT NO. | DATE | NAME | CLASS | SUBCLASS | FILING DATE |
|---------------------|------------|----------|------------------|-------|----------|-------------|
| | 4,698,766 | 10/06/87 | Entwistle et al. | | | 05/17/85 |
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| | 5,208,765 | 05/04/93 | Turnbull | | | 07/20/90 |
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| | 5,420,796 | 05/30/95 | Weling et al. | | | 12/23/93 |
| | 5,469,361 | 11/21/95 | Moyne | | | 06/06/94 |
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| | 0 621 522 A2 | 10/26/94 | Europe | | | X | |
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EXAMINER

Michael J. [Signature]

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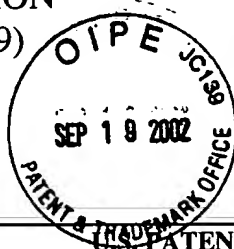
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ATTY. DOCKET NO.
5920/FET/DV

SERIAL NO.
09/943,383

APPLICANT
SHANMUGASUNDRAM et al.

FILING DATE
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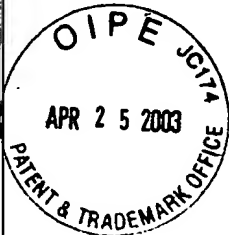
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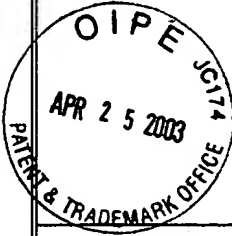
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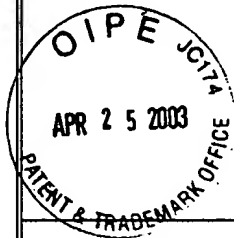
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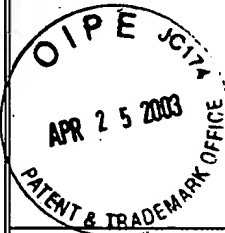
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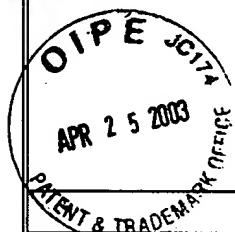
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